Christophe Detavernier

List of Publications by Year
in descending order

428 papers	12,719 citations	26567 56 h-index	46693 89 g-index
434 all docs	434 docs citations	434 times ranked	11905 citing authors

#	Article	IF	Citations
1	Towards implementation of a nickel silicide process for CMOS technologies. Microelectronic Engineering, 2003, 70, 144-157.	1.1	387
2	Super-dry reforming of methane intensifies CO ₂ utilization via Le Chatelierâ€™s principle. Science, 2016, 354, 449-452.	6.0	348
3	Tailoring nanoporous materials by atomic layer deposition. Chemical Society Reviews, 2011, 40, 5242.	18.7	338
4	Three-Dimensional Observation of the Conductive Filament in Nanoscaled Resistive Memory Devices. Nano Letters, 2014, 14, 2401-2406.	4.5	290
5	Barrier height inhomogeneities of epitaxial CoSi2 Schottky contacts on n-Si (100) and (111). Solid-State Electronics, 2000, 44, 663-671.	0.8	225
6	High-k dielectrics for future generation memory devices (Invited Paper). Microelectronic Engineering, 2009, 86, 1789-1795.	1.1	218
7	Atomic layer deposition of TiO2 from tetrakis-dimethyl-amido titanium or Ti isopropoxide precursors and H2O. Journal of Applied Physics, 2007, 102, .	1.1	214
8	Thin film reaction of transition metals with germanium. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2006, 24, 474-485.	0.9	208
9	An off-normal fibre-like texture in thin films on single-crystal substrates. Nature, 2003, 426, 641-645.	13.7	181
10	Atomic layer deposition of titanium nitride from TDMAT precursor. Microelectronic Engineering, 2009, 86, 72-77.	1.1	149
11	CeO₂-Modified Fe₂O₃ for CO₂ Utilization via Chemical Looping. Industrial & Engineering Chemistry Research, 2013, 52, 8416-8426.	1.8	149
12	In-situ X-ray Diffraction study of Metal Induced Crystallization of amorphous silicon. Thin Solid Films, 2008, 516, 4946-4952.	0.8	140
13	Germanium surface passivation and atomic layer deposition of high-<i>k</i>dielectricsâ€"a tutorial review on Ge-based MOS capacitors. Semiconductor Science and Technology, 2012, 27, 074012.	1.0	138
14	Effects of additive elements on the phase formation and morphological stability of nickel monosilicide films. Microelectronic Engineering, 2006, 83, 2042-2054.	1.1	121
15	Plasma-enhanced chemical vapour deposition growth of Si nanowires with low melting point metal catalysts: an effective alternative to Au-mediated growth. Nanotechnology, 2007, 18, 505307.	1.3	120
16	Growth Kinetics and Crystallization Behavior of TiO[sub 2] Films Prepared by Plasma Enhanced Atomic Layer Deposition. Journal of the Electrochemical Society, 2008, 155, H688.	1.3	111
17	Catalyst-assisted chemical looping for CO2 conversion to CO. Applied Catalysis B: Environmental, 2015, 164, 184-191.	10.8	110
18	High-temperature degradation of NiSi films: Agglomeration versus NiSi2 nucleation. Journal of Applied Physics, 2005, 98, 033526.	1.1	106

#	Article	IF	Citations
19	<i>In situ</i> x-ray diffraction study of metal induced crystallization of amorphous germanium. Journal of Applied Physics, 2009, 105, .	1.1	103
20	The coordinatively saturated vanadium MIL-47 as a low leaching heterogeneous catalyst in the oxidation of cyclohexene. Journal of Catalysis, 2012, 285, 196-207.	3.1	100
21	Delivering a Modifying Element to Metal Nanoparticles via Support: Ptâ€“Ga Alloying during the Reduction of Pt/Mg(Al,Ga)O_{<i>x</i>} Catalysts and Its Effects on Propane Dehydrogenation. ACS Catalysis, 2014, 4, 1812-1824.	5.5	100
22	Independent tuning of size and coverage of supported Pt nanoparticles using atomic layer deposition. Nature Communications, 2017, 8, 1074.	5.8	95
23	Influence of Pt addition on the texture of NiSi on Si(001). Applied Physics Letters, 2004, 84, 3549-3551.	1.5	93
24	Modeling the Conformality of Atomic Layer Deposition: The Effect of Sticking Probability. Journal of the Electrochemical Society, 2009, 156, P63.	1.3	92
25	Conformality of Al[sub 2]O[sub 3] and AlN Deposited by Plasma-Enhanced Atomic Layer Deposition. Journal of the Electrochemical Society, 2010, 157, G111.	1.3	91
26	Low-Temperature Atomic Layer Deposition of Platinum Using (Methylcyclopentadienyl)trimethylplatinum and Ozone. Journal of Physical Chemistry C, 2013, 117, 20557-20561.	1.5	90
27	Influence of the Cu-Te composition and microstructure on the resistive switching of Cu-Te/Al2O3/Si cells. Applied Physics Letters, 2011, 99, .	1.5	89
28	Controlling the stability of a Feâ€“Ni reforming catalyst: Structural organization of the active components. Applied Catalysis B: Environmental, 2017, 209, 405-416.	10.8	89
29	Reactor concepts for atomic layer deposition on agitated particles: A review. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, .	0.9	85
30	Ballistic electron emission microscopy study of barrier height inhomogeneities introduced in Au/n-Si Schottky contacts by a HF pretreatment. Journal of Applied Physics, 1998, 84, 3226-3231.	1.1	82
31	Influence of mixing entropy on the nucleation ofCoSi2. Physical Review B, 2000, 62, 12045-12051.	1.1	78
32	Semiconductor-metal transition in thin VO2 films grown by ozone based atomic layer deposition. Applied Physics Letters, 2011, 98, .	1.5	78
33	Optimizations of Pulsed Plated p and nâ€type Bi₂Te₃â€Based Ternary Compounds by Annealing in Different Ambient Atmospheres. Advanced Energy Materials, 2013, 3, 95-104.	10.2	77
34	Plasma enhanced atomic layer deposition of Ga₂O₃thin films. Journal of Materials Chemistry A, 2014, 2, 19232-19238.	5.2	77
35	A USB-controlled potentiostat/galvanostat for thin-film battery characterization. HardwareX, 2017, 2, 34-49.	1.1	76
36	Red Mn⁴⁺-Doped Fluoride Phosphors: Why Purity Matters. ACS Applied Materials & Interfaces, 2018, 10, 18845-18856.	4.0	74

#	Article	IF	Citations
37	Phase formation and thermal stability of ultrathin nickel-silicides on Si(100). Applied Physics Letters, 2010, 96, .	1.5	73
38	Amorphous and Crystalline Vanadium Oxides as High-Energy and High-Power Cathodes for Three-Dimensional Thin-Film Lithium Ion Batteries. ACS Applied Materials & Interfaces, 2017, 9, 13121-13131.	4.0	73
39	Metalâ€Insulator Transition in ALD VO₂ Ultrathin Films and Nanoparticles: Morphological Control. Advanced Functional Materials, 2015, 25, 679-686.	7.8	70
40	Selective and reversible ammonia gas detection with nanoporous film functionalized silicon photonic micro-ring resonator. Optics Express, 2012, 20, 11855.	1.7	69
41	Thermodynamics and kinetics of room-temperature microstructural evolution in copper films. Journal of Applied Physics, 2003, 94, 2874-2881.	1.1	67
42	Comparison of Thermal and Plasma-Enhanced ALD/CVD of Vanadium Pentoxide. Journal of the Electrochemical Society, 2009, 156, P122.	1.3	67
43	A BEEM study of the temperature dependence of the barrier height distribution in PtSi/n-Si Schottky diodes. Solid State Communications, 1999, 112, 611-615.	0.9	66
44	In Situ X-ray Fluorescence Measurements During Atomic Layer Deposition: Nucleation and Growth of TiO₂ on Planar Substrates and in Nanoporous Films. Journal of Physical Chemistry C, 2011, 115, 6605-6610.	1.5	66
45	Fe-Containing Magnesium Aluminate Support for Stability and Carbon Control during Methane Reforming. ACS Catalysis, 2018, 8, 5983-5995.	5.5	66
46	Electrical characteristics of CoSi2/n-Si(100) Schottky barrier contacts formed by solid state reaction. Solid-State Electronics, 2000, 44, 1807-1818.	0.8	63
47	Microencapsulation of Moisture-Sensitive CaS:Eu[sup 2+] Particles with Aluminum Oxide. Journal of the Electrochemical Society, 2009, 156, J333.	1.3	63
48	Optimization of Electrodeposited pâ€Doped Sb₂Te₃ Thermoelectric Films by Millisecond Potentiostatic Pulses. Advanced Energy Materials, 2012, 2, 345-352.	10.2	63
49	Partially fluorinated MIL-47 and Al-MIL-53 frameworks: influence of functionalization on sorption and breathing properties. Physical Chemistry Chemical Physics, 2013, 15, 3552.	1.3	63
50	Reaction of thin Ni films with Ge: Phase formation and texture. Journal of Applied Physics, 2006, 100, 034306.	1.1	62
51	Thermal expansion of the isostructural PtSi and NiSi: Negative expansion coefficient in NiSi and stress effects in thin films. Journal of Applied Physics, 2003, 93, 2510-2515.	1.1	61
52	Understanding the Dual Nature of the Filament Dissolution in Conductive Bridging Devices. Journal of Physical Chemistry Letters, 2015, 6, 1919-1924.	2.1	61
53	Plasmonic gold-embedded TiO2 thin films as photocatalytic self-cleaning coatings. Applied Catalysis B: Environmental, 2020, 267, 118654.	10.8	61
54	Tuning the Pore Size of Ink-Bottle Mesopores by Atomic Layer Deposition. Chemistry of Materials, 2012, 24, 1992-1994.	3.2	59

#	Article	IF	Citations
55	Voltage-Controlled ONâ€“OFF Ferromagnetism at Room Temperature in a Single Metal Oxide Film. ACS Nano, 2018, 12, 10291-10300.	7.3	57
56	Formation and morphological stability of NiSi in the presence of W, Ti, and Ta alloying elements. Journal of Applied Physics, 2007, 101, 044508.	1.1	56
57	Composition influence on the physical and electrical properties of SrxTi1âˆ’xOy-based metal-insulator-metal capacitors prepared by atomic layer deposition using TiN bottom electrodes. Journal of Applied Physics, 2009, 106, 094101.	1.1	56
58	Deactivation Study of Fe₂O₃â€“CeO₂ during Redox Cycles for CO Production from CO₂. Industrial & Engineering Chemistry Research, 2016, 55, 5911-5922.	1.8	56
59	Air-stable short-wave infrared PbS colloidal quantum dot photoconductors passivated with Al2O3 atomic layer deposition. Applied Physics Letters, 2014, 105, .	1.5	55
60	In situ X-ray diffraction study of the controlled oxidation and reduction in the Vâ€“O system for the synthesis of VO₂ and V₂O₃ thin films. Journal of Materials Chemistry C, 2015, 3, 11357-11365.	2.7	55
61	Atomic layer deposition-enabled single layer of tungsten trioxide across a large area. Applied Materials Today, 2017, 6, 44-53.	2.3	52
62	<i>In Situ</i> Monitoring of Atomic Layer Deposition in Nanoporous Thin Films Using Ellipsometric Porosimetry. Langmuir, 2012, 28, 3852-3859.	1.6	51
63	ALD-grown seed layers for electrochemical copper deposition integrated with different diffusion barrier systems. Microelectronic Engineering, 2011, 88, 684-689.	1.1	50
64	The Influence of Ultrathin Amorphous ALD Alumina and Titania on the Rate Capability of Anatase TiO₂ and LiMn₂O₄ Lithium Ion Battery Electrodes. Advanced Materials Interfaces, 2017, 4, 1601237.	1.9	50
65	Ru thin film grown on TaN by plasma enhanced atomic layer deposition. Thin Solid Films, 2009, 517, 4689-4693.	0.8	49
66	Chemically Triggered Formation of Two-Dimensional Epitaxial Quantum Dot Superlattices. ACS Nano, 2016, 10, 6861-6870.	7.3	49
67	Atomic layer deposition-based synthesis of photoactive TiO2 nanoparticle chains by using carbon nanotubes as sacrificial templates. RSC Advances, 2014, 4, 11648.	1.7	48
68	Silver-polymer core-shell nanoparticles for ultrastable plasmon-enhanced photocatalysis. Applied Catalysis B: Environmental, 2017, 200, 31-38.	10.8	48
69	Catalyst-assisted chemical looping auto-thermal dry reforming: Spatial structuring effects on process efficiency. Applied Catalysis B: Environmental, 2018, 231, 123-136.	10.8	48
70	Atomic layer deposition of ZnOâ€“SnO2 composite thin film: The influence of structure, composition and crystallinity on lithium-ion battery performance. Electrochimica Acta, 2019, 320, 134604.	2.6	48
71	Room-temperature grain growth in sputter-deposited Cu films. Applied Physics Letters, 2003, 82, 1863-1865.	1.5	47
72	Pt redistribution during Ni(Pt) silicide formation. Applied Physics Letters, 2008, 93, .	1.5	47

#	Article	IF	Citations
73	Atomic layer deposition of vanadium oxides: process and application review. Materials Today Chemistry, 2019, 12, 396-423.	1.7	46
74	Air-based photoelectrochemical cell capturing water molecules from ambient air for hydrogen production. RSC Advances, 2014, 4, 29286-29290.	1.7	45
75	Molecular layer deposition of â€œtitaniconeâ€, a titanium-based hybrid material, as an electrode for lithium-ion batteries. Dalton Transactions, 2016, 45, 1176-1184.	1.6	45
76	Ovonic Thresholdâ€Switching Ge_{<i>x</i>}Se_{<i>y</i>} Chalcogenide Materials: Stoichiometry, Trap Nature, and Material Relaxation from First Principles. Physica Status Solidi - Rapid Research Letters, 2020, 14, 1900672.	1.2	45
77	CoSi2 formation in the Ti/Co/SiO2/Si system. Journal of Applied Physics, 2000, 88, 133-140.	1.1	44
78	Ultra-low-k cyclic carbon-bridged PMO films with a high chemical resistance. Journal of Materials Chemistry, 2012, 22, 8281.	6.7	44
79	Surface engineering of low enriched uraniumâ€“molybdenum. Journal of Nuclear Materials, 2013, 440, 220-228.	1.3	44
80	Atomic layer deposition-based tuning of the pore size in mesoporous thin films studied by in situ grazing incidence small angle X-ray scattering. Nanoscale, 2014, 6, 14991-14998.	2.8	44
81	Plasma-Enhanced Atomic Layer Deposition of Iron Phosphate as a Positive Electrode for 3D Lithium-Ion Microbatteries. Chemistry of Materials, 2016, 28, 3435-3445.	3.2	44
82	Atomic Layer Deposition Route To Tailor Nanoalloys of Noble and Non-noble Metals. ACS Nano, 2016, 10, 8770-8777.	7.3	44
83	Manganese oxide films with controlled oxidation state for water splitting devices through a combination of atomic layer deposition and post-deposition annealing. RSC Advances, 2016, 6, 98337-98343.	1.7	44
84	Plasma enhanced atomic layer deposition of Fe₂O₃ thin films. Journal of Materials Chemistry A, 2014, 2, 10662-10667.	5.2	43
85	A rotary reactor for thermal and plasma-enhanced atomic layer deposition on powders and small objects. Surface and Coatings Technology, 2012, 213, 183-191.	2.2	42
86	Swelling of U(Mo) dispersion fuel under irradiation â€“ Non-destructive analyses of the SELENIUM plates. Journal of Nuclear Materials, 2013, 442, 60-68.	1.3	42
87	Molecular layer deposition of â€œvanadiconeâ€, a vanadium-based hybrid material, as an electrode for lithium-ion batteries. Dalton Transactions, 2017, 46, 4542-4553.	1.6	42
88	Stabilizing Fluoride Phosphors: Surface Modification by Atomic Layer Deposition. Chemistry of Materials, 2019, 31, 7192-7202.	3.2	42
89	Epitaxial Formation of a Metastable Hexagonal Nickelâ€“Silicide. Electrochemical and Solid-State Letters, 2008, 11, H266.	2.2	41
90	The effects of deposition temperature and ambient onÂtheÂphysicalÂand electrical performance ofÂDC-sputteredÂn-ZnO/p-Si heterojunction. Applied Physics A: Materials Science and Processing, 2010, 98, 357-365.	1.1	41

#	Article	IF	Citations
91	Implementing TiO2 as gate dielectric for Ge-channel complementary metal-oxide-semiconductor devices by using HfO2/GeO2 interlayer. Applied Physics Letters, 2010, 97, .	1.5	41
92	Fuel swelling and interaction layer formation in the SELENIUM Si and ZrN coated U(Mo) dispersion fuel plates irradiated at high power in BR2. Journal of Nuclear Materials, 2015, 458, 380-393.	1.3	41
93	A core-shell structured Fe 2 O 3 /ZrO 2 @ZrO 2 nanomaterial with enhanced redox activity and stability for CO 2 conversion. Journal of CO2 Utilization, 2017, 17, 20-31.	3.3	41
94	Ultra-thin sub-10â€‰nm Ga2O3-WO3 heterostructures developed by atomic layer deposition for sensitive and selective C2H5OH detection on ppm level. Sensors and Actuators B: Chemical, 2019, 287, 147-156.	4.0	41
95	Deposition of MnO Anode and MnO₂ Cathode Thin Films by Plasma Enhanced Atomic Layer Deposition Using the Mn(thd)₃ Precursor. Chemistry of Materials, 2015, 27, 3628-3635.	3.2	40
96	The transformation behaviour of â€œaluconesâ€ deposited by molecular layer deposition, in nanoporous Al₂O₃layers. Dalton Transactions, 2018, 47, 5860-5870.	1.6	40
97	The effect of silicon on the interaction between metallic uranium and aluminum: A 50 year long diffusion experiment. Journal of Nuclear Materials, 2008, 381, 242-248.	1.3	39
98	Aluminium atomic layer deposition applied to mesoporous zeolites for acid catalytic activity enhancement. Catalysis Science and Technology, 2011, 1, 218.	2.1	39
99	Influence of Ti on CoSi2 nucleation. Applied Physics Letters, 2000, 77, 3170-3172.	1.5	38
100	Solid-state formation of titanium carbide and molybdenum carbide as contacts for carbon-containing semiconductors. Journal of Applied Physics, 2006, 99, 063704.	1.1	38
101	Influence of a transient hexagonal phase on the microstructure and morphological stability of NiSi films. Applied Physics Letters, 2009, 94, .	1.5	38
102	Plasma-Enhanced ALD of Platinum with O₂, N₂and NH₃Plasmas. ECS Journal of Solid State Science and Technology, 2012, 1, Q123-Q129.	0.9	38
103	Influence of Carbon Alloying on the Thermal Stability and Resistive Switching Behavior of Copper-Telluride Based CBRAM Cells. ACS Applied Materials & Interfaces, 2013, 5, 6984-6989.	4.0	38
104	Atomic Layer Deposition of Pt Nanoparticles within the Cages of MIL-101: A Mild and Recyclable Hydrogenation Catalyst. Nanomaterials, 2016, 6, 45.	1.9	38
105	Acidâ€“Base Mediated Ligand Exchange on Near-Infrared Absorbing, Indium-Based IIIâ€“V Colloidal Quantum Dots. Journal of the American Chemical Society, 2021, 143, 4290-4301.	6.6	38
106	Atomic Layer Deposition of Aluminum Phosphate Based on the Plasma Polymerization of Trimethyl Phosphate. Chemistry of Materials, 2014, 26, 6863-6871.	3.2	37
107	Photocatalytic acetaldehyde oxidation in air using spacious TiO2 films prepared by atomic layer deposition on supported carbonaceous sacrificial templates. Applied Catalysis B: Environmental, 2014, 160-161, 204-210.	10.8	37
108	Low Temperature Atomic Layer Deposition of Crystalline In₂O₃ Films. Journal of Physical Chemistry C, 2015, 119, 11786-11791.	1.5	37

#	Article	IF	Citations
109	Bifunctional Co- and Ni- ferrites for catalyst-assisted chemical looping with alcohols. Applied Catalysis B: Environmental, 2018, 222, 59-72.	10.8	36
110	Nucleation Enhancement and Area-Selective Atomic Layer Deposition of Ruthenium Using RuO₄ and H₂ Gas. Chemistry of Materials, 2019, 31, 1491-1499.	3.2	36
111	The influence of Ti capping layers on CoSi2 formation. Microelectronic Engineering, 2000, 50, 125-132.	1.1	35
112	Atomic layer deposition of ruthenium at 100 Â°C using the RuO₄-precursor and H₂. Journal of Materials Chemistry C, 2015, 3, 132-137.	2.7	35
113	ALD assisted nanoplasmonic slot waveguide for on-chip enhanced Raman spectroscopy. APL Photonics, 2018, 3, .	3.0	35
114	CoSi2 formation in the presence of interfacial silicon oxide. Applied Physics Letters, 1999, 74, 2930-2932.	1.5	34
115	<i>In situ</i> synchrotron based x-ray techniques as monitoring tools for atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, .	0.9	34
116	K₂MnF₆ as a precursor for saturated red fluoride phosphors: the struggle for structural stability. Journal of Materials Chemistry C, 2017, 5, 10761-10769.	2.7	34
117	Plasmonic Near-Field Localization of Silver Coreâ€“Shell Nanoparticle Assemblies via Wet Chemistry Nanogap Engineering. ACS Applied Materials & Interfaces, 2017, 9, 41577-41585.	4.0	34
118	Electron Transfer and Near-Field Mechanisms in Plasmonic Gold-Nanoparticle-Modified TiO₂ Photocatalytic Systems. ACS Applied Nano Materials, 2019, 2, 4067-4074.	2.4	34
119	In situ XAS and XRF study of nanoparticle nucleation during O3-based Pt deposition. Catalysis Today, 2014, 229, 2-13.	2.2	33
120	A Case Study of ALD Encapsulation of Quantum Dots: Embedding Supported CdSe/CdS/ZnS Quantum Dots in a ZnO Matrix. Journal of Physical Chemistry C, 2016, 120, 18039-18045.	1.5	33
121	Microwave induced â€œegg yolkâ€•structure in Cr/V-MIL-53. Chemical Communications, 2017, 53, 8478-8481.	2.2	33
122	Thin film solid-state reactions forming carbides as contact materials for carbon-containing semiconductors. Journal of Applied Physics, 2007, 101, 053714.	1.1	32
123	Switching mechanism and reverse engineering of low-power Cu-based resistive switching devices. Nanoscale, 2013, 5, 11187.	2.8	32
124	Heterogeneous TiO₂/V₂O₅/Carbon Nanotube Electrodes for Lithium-Ion Batteries. ACS Applied Materials & Interfaces, 2017, 9, 8055-8064.	4.0	32
125	Plasma-enhanced atomic layer deposition of titanium phosphate as an electrode for lithium-ion batteries. Journal of Materials Chemistry A, 2017, 5, 330-338.	5.2	31
126	Formation and Functioning of Bimetallic Nanocatalysts: The Power of Xâ€ray Probes. Angewandte Chemie - International Edition, 2019, 58, 13220-13230.	7.2	31

#	Article	IF	Citations
127	Colloidal IIIâ€“V Quantum Dot Photodiodes for Shortâ€Wave Infrared Photodetection. Advanced Science, 2022, 9, e2200844.	5.6	31
128	Thermal and Plasma-Enhanced Atomic Layer Deposition of TiN Using TDMAT and NH₃ on Particles Agitated in a Rotary Reactor. ACS Applied Materials & Interfaces, 2014, 6, 7316-7324.	4.0	30
129	Crystallization and semiconductor-metal switching behavior of thin VO2 layers grown by atomic layer deposition. Thin Solid Films, 2014, 550, 59-64.	0.8	30
130	Texture in thin film silicides and germanides: A review. Applied Physics Reviews, 2016, 3, 031302.	5.5	30
131	Reactive Diffusion in the Ni-Si System: Phase Sequence and Formation of Metal-Rich Phases. Defect and Diffusion Forum, 2005, 237-240, 825-836.	0.4	29
132	Influence of Ge substrate crystallinity on Co germanide formation in solid-state reactions. Applied Physics Letters, 2007, 90, 031906.	1.5	29
133	Embedding Quantum Dot Monolayers in Al₂O₃ Using Atomic Layer Deposition. Chemistry of Materials, 2011, 23, 126-128.	3.2	29
134	Conformality of thermal and plasma enhanced atomic layer deposition on a non-woven fibrous substrate. Surface and Coatings Technology, 2012, 206, 4511-4517.	2.2	29
135	Factors Influencing the Conductivity of Aqueous Sol(ution)â€“Gel-Processed Al-Doped ZnO Films. Chemistry of Materials, 2014, 26, 5839-5851.	3.2	29
136	Formation of epitaxial CoSi2 by a Cr or Mo interlayer: Comparison with a Ti interlayer. Journal of Applied Physics, 2001, 89, 2146-2150.	1.1	28
137	In Situ IR Spectroscopic Investigation of Alumina ALD on Porous Silica Films: Thermal versus Plasma-Enhanced ALD. Journal of Physical Chemistry C, 2014, 118, 29854-29859.	1.5	28
138	Unravelling the Formation of Ptâ€“Ga Alloyed Nanoparticles on Calcined Ga-Modified Hydrotalcites by <i>in Situ</i> XAS. Chemistry of Materials, 2014, 26, 5936-5949.	3.2	28
139	Direct Imaging of ALD Deposited Pt Nanoclusters inside the Giant Pores of MILâ€101. Particle and Particle Systems Characterization, 2016, 33, 382-387.	1.2	28
140	Effective reduction of fixed charge densities in germanium based metal-oxide-semiconductor devices. Applied Physics Letters, 2011, 99, .	1.5	27
141	Atomic layer deposited second-order nonlinear optical metamaterial for back-end integration with CMOS-compatible nanophotonic circuitry. Optics Letters, 2015, 40, 5371.	1.7	27
142	Atomic layer deposition of vanadium oxides for thin-film lithium-ion battery applications. RSC Advances, 2016, 6, 114658-114665.	1.7	27
143	CoSi2 formation through SiO2. Thin Solid Films, 2001, 386, 19-26.	0.8	26
144	Texture of tetragonalÎ±âˆ’FeSi2films on Si(001). Physical Review B, 2004, 69, .	1.1	26

#	Article	IF	Citations
145	The influence of Pt redistribution on Ni1âˆ’xPtxSi growth properties. Journal of Applied Physics, 2010, 108, .	1.1	26
146	Anisotropic Atomic Layer Deposition Profiles of TiO₂ in Hierarchical Silica Material with Multiple Porosity. Chemistry of Materials, 2012, 24, 2775-2780.	3.2	26
147	Scanning probe microscopy as a scalpel to probe filament formation in conductive bridging memory devices. Microelectronic Engineering, 2014, 120, 67-70.	1.1	26
148	<i>In Situ</i> Electron Paramagnetic Resonance and X-ray Diffraction Monitoring of Temperature-Induced Breathing and Related Structural Transformations in Activated V-Doped MIL-53(Al). Journal of Physical Chemistry C, 2016, 120, 17400-17407.	1.5	26
149	FeO controls the sintering of iron-based oxygen carriers in chemical looping CO2 conversion. Journal of CO2 Utilization, 2020, 40, 101216.	3.3	26
150	Ultrathin GeOxNy interlayer formed by <i>in situ</i>â€ˆNH3 plasma pretreatment for passivation of germanium metal-oxide-semiconductor devices. Applied Physics Letters, 2010, 97, .	1.5	25
151	Thermal-stability optimization of Al2O3/Cuâ€“Te based conductive-bridging random access memory systems. Thin Solid Films, 2013, 533, 29-33.	0.8	25
152	Porous nanostructured metal oxides synthesized through atomic layer deposition on a carbonaceous template followed by calcination. Journal of Materials Chemistry A, 2015, 3, 2642-2649.	5.2	25
153	Key role of surface oxidation and reduction processes in the coarsening of Pt nanoparticles. Nanoscale, 2017, 9, 13159-13170.	2.8	25
154	Spacious and mechanically flexible mesoporous silica thin film composed of an open network of interlinked nanoslabs. Journal of Materials Chemistry, 2011, 21, 7692.	6.7	24
155	<i>In situ</i> synchrotron based x-ray fluorescence and scattering measurements during atomic layer deposition: Initial growth of HfO2 on Si and Ge substrates. Applied Physics Letters, 2011, 98, .	1.5	24
156	Catalytic activation of OKO zeolite with intersecting pores of 10- and 12-membered rings using atomic layer deposition of aluminium. Chemical Communications, 2014, 50, 4610-4612.	2.2	24
157	Combinatorial Study of Agâ€“Te Thin Films and Their Application as Cation Supply Layer in CBRAM Cells. ACS Combinatorial Science, 2015, 17, 334-340.	3.8	24
158	Monte Carlo simulations of atomic layer deposition on 3D large surface area structures: Required precursor exposure for pillar- versus hole-type structures. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	24
159	Sensing the framework state and guest molecules in MIL-53(Al) via the electron paramagnetic resonance spectrum of V^{IV} dopant ions. Physical Chemistry Chemical Physics, 2017, 19, 24545-24554.	1.3	24
160	Ligand Binding to Copper Nanocrystals: Amines and Carboxylic Acids and the Role of Surface Oxides. Chemistry of Materials, 2019, 31, 2058-2067.	3.2	24
161	Bifunctional earth-abundant phosphate/phosphide catalysts prepared <i>via</i> atomic layer deposition for electrocatalytic water splitting. Nanoscale Advances, 2019, 1, 4166-4172.	2.2	24
162	Annealing effect on the metal gate effective work function modulation for the Al/TiN/SiO2/p-Si structure. Microelectronic Engineering, 2011, 88, 573-577.	1.1	23

#	ARTICLE	IF	CITATIONS
163	Atomic Layer Deposition of Titanium and Vanadium Oxide on Mesoporous Silica and Phenol/Formaldehyde Resins - the Effect of the Support on the Liquid Phase Epoxidation of Cyclohexene. European Journal of Inorganic Chemistry, 2012, 2012, 251-260.	1.0	23
164	Synthesis of uniformly dispersed anatase nanoparticles inside mesoporous silica thin films via controlled breakup and crystallization of amorphous TiO2 deposited using atomic layer deposition. Nanoscale, 2013, 5, 5001.	2.8	23
165	A Single-Event MicroKinetic assessment of n-alkane hydroconversion on ultrastable Y zeolites after Atomic Layer Deposition of alumina. Journal of Catalysis, 2014, 311, 433-446.	3.1	23
166	Study of metal-related deep-level defects in germanide Schottky barriers on n-type germanium. Journal of Applied Physics, 2008, 104, .	1.1	22
167	A new procedure to seal the pores of mesoporous low-k films with precondensed organosilica oligomers. Chemical Communications, 2012, 48, 2797.	2.2	22
168	Controllable nitrogen doping in as deposited TiO2 film and its effect on post deposition annealing. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2014, 32, .	0.9	22
169	Plasma enhanced atomic layer deposition of aluminum sulfide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	0.9	22
170	Pore pressure estimation in irradiated UMo. Journal of Nuclear Materials, 2018, 510, 472-483.	1.3	22
171	Setting Carriers Free: Healing Faulty Interfaces Promotes Delocalization and Transport in Nanocrystal Solids. ACS Nano, 2019, 13, 12774-12786.	7.3	22
172	Hierarchical Fe-modified MgAl₂O₄ as a Ni-catalyst support for methane dry reforming. Catalysis Science and Technology, 2020, 10, 6987-7001.	2.1	22
173	Deep level transient spectroscopy study of nickel-germanide Schottky barriers on n-type germanium. Applied Physics Letters, 2006, 88, 183506.	1.5	21
174	Texture of NiSi films on Si(001), (111), and (110) substrates. Journal of Applied Physics, 2008, 103, 113526.	1.1	21
175	Thermal Versus Plasma-Enhanced ALD: Growth Kinetics and Conformality. ECS Transactions, 2008, 16, 239-246.	0.3	21
176	Three dimensional reciprocal space measurement by x-ray diffraction using linear and area detectors: Applications to texture and defects determination in oriented thin films and nanoprecipitates. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, 021505.	0.9	21
177	Mobile setup for synchrotron based <i>in situ</i> characterization during thermal and plasma-enhanced atomic layer deposition. Review of Scientific Instruments, 2016, 87, 113905.	0.6	21
178	Plasma enhanced atomic layer deposition of zinc sulfide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	21
179	Controlling the formation and stability of ultra-thin nickel silicides - An alloying strategy for preventing agglomeration. Journal of Applied Physics, 2018, 123, .	1.1	21
180	Selective electroless deposition of cobalt using amino-terminated SAMs. Journal of Materials Chemistry C, 2019, 7, 4392-4402.	2.7	21

#	Article	IF	Citations
181	Atomic Layer Deposition on Polymer Thin Films: On the Role of Precursor Infiltration and Reactivity. ACS Applied Materials & Interfaces, 2021, 13, 46151-46163.	4.0	21
182	CoSi2 formation in the presence of carbon. Journal of Applied Physics, 2002, 92, 1207-1211.	1.1	20
183	Low-temperature formation of CoSi2 in the presence of Au. Journal of Applied Physics, 2004, 95, 5340-5346.	1.1	20
184	Axiotaxy of CoSi2 thin films on Si(100) substrates and the effects of Ti alloying. Journal of Applied Physics, 2004, 95, 8376-8381.	1.1	20
185	Texture of Cobalt Germanides on Ge(100) and Ge(111) and Its Influence on the Formation Temperature. Journal of the Electrochemical Society, 2010, 157, H395.	1.3	20
186	Effect of annealing atmosphere on LiMn₂O₄ for thin film Li-ion batteries from aqueous chemical solution deposition. Journal of Materials Chemistry A, 2016, 4, 18457-18469.	5.2	20
187	Plasma-Enhanced Atomic Layer Deposition of Silver Using Ag(fod)(PEt₃) and NH₃-Plasma. Chemistry of Materials, 2017, 29, 7114-7121.	3.2	20
188	Surface species during ALD of platinum observed with <i>in situ</i> reflection IR spectroscopy. Physical Chemistry Chemical Physics, 2018, 20, 25343-25356.	1.3	20
189	CoSi2 nucleation in the presence of Ge. Thin Solid Films, 2001, 384, 243-250.	0.8	19
190	Mixing entropy and the nucleation of silicides: Niâ€“Pdâ€“Si and Coâ€“Mnâ€“Si ternary systems. Journal of Materials Research, 2003, 18, 1668-1678.	1.2	19
191	High-Performance Ge MOS Capacitors by $hbox{O}_{2}$ Plasma Passivation and $hbox{O}_{2}$ Ambient Annealing. IEEE Electron Device Letters, 2011, 32, 1656-1658.	2.2	19
192	Effective Electrical Passivation of Ge(100) for HfO2 Gate Dielectric Layers Using O2 Plasma. Electrochemical and Solid-State Letters, 2011, 14, G20.	2.2	19
193	Atomic Layer Deposition of TiO₂ on Surface Modified Nanoporous Low-<i>k</i> Films. Langmuir, 2013, 29, 12284-12289.	1.6	19
194	Progressive vs. abrupt reset behavior in conductive bridging devices: A C-AFM tomography study. , 2014, , .		19
195	Magnetic characterization and electrical field-induced switching of magnetite thin films synthesized by atomic layer deposition and subsequent thermal reduction. Journal Physics D: Applied Physics, 2014, 47, 485001.	1.3	19
196	Near room temperature plasma enhanced atomic layer deposition of ruthenium using the RuO₄-precursor and H₂-plasma. Journal of Materials Chemistry C, 2015, 3, 4848-4851.	2.7	19
197	One-pot synthesis of Pt catalysts based on layered double hydroxides: an application in propane dehydrogenation. Catalysis Science and Technology, 2016, 6, 1863-1869.	2.1	19
198	Surface mobility and impact of precursor dosing during atomic layer deposition of platinum:<i>in situ</i>monitoring of nucleation and island growth. Physical Chemistry Chemical Physics, 2020, 22, 24917-24933.	1.3	19

#	Article	IF	Citations
199	Thermal stability, phase and interface uniformity of Ni-silicide formed by Niâ€“Si solid-state reaction. Thin Solid Films, 2004, 462-463, 146-150.	0.8	18
200	Diffusion barrier properties of TaNx films prepared by plasma enhanced atomic layer deposition from PDMAT with N2 or NH3 plasma. Microelectronic Engineering, 2008, 85, 2059-2063.	1.1	18
201	The role of lattice mismatch and kinetics in texture development: Co1â^'xNixSi2 thin films on Si(100). Journal of Applied Physics, 2008, 103, .	1.1	18
202	Doped GeSe materials for selector applications. , 2017, , .		18
203	Redox Layer Deposition of Thin Films of MnO₂ on Nanostructured Substrates from Aqueous Solutions. Chemistry of Materials, 2019, 31, 4805-4816.	3.2	18
204	Boosting Roomâ€Temperature Magnetoâ€Ionics in a Nonâ€Magnetic Oxide Semiconductor. Advanced Functional Materials, 2020, 30, 2003704.	7.8	18
205	Study of the surface species during thermal and plasma-enhanced atomic layer deposition of titanium oxide films using <i>in situ</i> IR-spectroscopy and <i>in vacuo</i> X-ray photoelectron spectroscopy. Physical Chemistry Chemical Physics, 2020, 22, 9262-9271.	1.3	18
206	A BEEM study of Schottky barrier height distributions of ultrathin CoSi2/n-Si(100) formed by solid phase epitaxy. Semiconductor Science and Technology, 2000, 15, 349-356.	1.0	17
207	Characterization of the texture of silicide films using electron backscattered diffraction. Applied Physics Letters, 2007, 90, 121920.	1.5	17
208	Texture of atomic layer deposited ruthenium. Microelectronic Engineering, 2010, 87, 1879-1883.	1.1	17
209	On the growth kinetics of Ni(Pt) silicide thin films. Journal of Applied Physics, 2013, 113, .	1.1	17
210	Plasma-enhanced atomic layer deposition of zinc phosphate. Journal of Non-Crystalline Solids, 2016, 444, 43-48.	1.5	17
211	Fe₂O₃â€“MgAl₂O₄ for CO Production from CO₂: MÃ¶ssbauer Spectroscopy and in Situ X-ray Diffraction. ACS Sustainable Chemistry and Engineering, 2019, 7, 9553-9565.	3.2	17
212	Molecular Layer Deposition of â€œMagnesiconeâ€, a Magnesium-based Hybrid Material. Chemistry of Materials, 2020, 32, 4451-4466.	3.2	17
213	Influence of processing conditions on CoSi2 formation in the presence of a Ti capping layer. Microelectronic Engineering, 2004, 71, 252-261.	1.1	16
214	Determination of the dominant diffusing species during nickel and palladium germanide formation. Thin Solid Films, 2012, 526, 261-268.	0.8	16
215	Phase formation and texture of thin nickel germanides on Ge(001) and Ge(111). Journal of Applied Physics, 2016, 119, .	1.1	16
216	PdZn nanoparticle catalyst formation for ethanol dehydrogenation: Active metal impregnation vs incorporation. Applied Catalysis A: General, 2018, 555, 12-19.	2.2	16

#	Article	IF	Citations
217	Annealing of thin â€œTinconeâ€•films, a tin-based hybrid material deposited by molecular layer deposition, in reducing, inert, and oxidizing atmospheres. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, 051506.	0.9	16
218	CO2 sorption properties of Li4SiO4 with a Li2ZrO3 coating. Journal of CO2 Utilization, 2019, 34, 688-699.	3.3	16
219	Plasma enhanced atomic layer deposition of gallium sulfide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	16
220	Waveguideâ€Coupled Colloidal Quantum Dot Light Emitting Diodes and Detectors on a Silicon Nitride Platform. Laser and Photonics Reviews, 2021, 15, 2000230.	4.4	16
221	CoSi2 formation in the presence of Ti, Ta or W. Thin Solid Films, 2004, 468, 174-182.	0.8	15
222	Effect of Pt addition on growth stress and thermal stress of NiSi films. Journal of Applied Physics, 2008, 104, 053510.	1.1	15
223	Interdiffusion and crystallization in HfO2/Al2O3 superlattices. Applied Physics Letters, 2009, 95, 091911.	1.5	15
224	Growth and Material Characterization of Hafnium Titanates Deposited by Atomic Layer Deposition. Journal of the Electrochemical Society, 2009, 156, G145.	1.3	15
225	Sn diffusion during Ni germanide growth on Ge1â€“xSnx. Applied Physics Letters, 2011, 99, 211905.	1.5	15
226	Low temperature plasma-enhanced atomic layer deposition of thin vanadium nitride layers for copper diffusion barriers. Applied Physics Letters, 2013, 102, 111910.	1.5	15
227	Improved thermal stability and retention properties of Cuâ€“Te based CBRAM by Ge alloying. Journal of Materials Chemistry C, 2015, 3, 12469-12476.	2.7	15
228	Hydroisomerization and hydrocracking activity enhancement of a hierarchical ZSM-5 zeolite catalyst via atomic layer deposition of aluminium. Catalysis Science and Technology, 2016, 6, 6177-6186.	2.1	15
229	TiO₂-coated luminescent porous silicon micro-particles as a promising system for nanomedicine. Journal of Materials Chemistry B, 2018, 6, 1815-1824.	2.9	15
230	Kinetics of Lifetime Changes in Bimetallic Nanocatalysts Revealed by Quick Xâ€ray Absorption Spectroscopy. Angewandte Chemie - International Edition, 2018, 57, 12430-12434.	7.2	15
231	Atomic Layer Deposition of Indiumâ€Tinâ€Oxide as Multifunctional Coatings on V₂O₅ Thinâ€Film Model Electrode for Lithiumâ€Ion Batteries. Advanced Materials Interfaces, 2020, 7, 2001022.	1.9	15
232	Properties of ultrathin molybdenum films for interconnect applications. Materialia, 2022, 24, 101511.	1.3	15
233	Effect of metal liner on electromigration in Cu Damascene lines. Journal of Applied Physics, 2005, 98, 124501.	1.1	14
234	The Deposition of Ru and RuO₂ Films for DRAM Electrode. ECS Transactions, 2010, 33, 135-144.	0.3	14

#	Article	IF	Citations
235	Phase formation and texture of nickel silicides on Si1â^'xCx epilayers. Microelectronic Engineering, 2011, 88, 536-540.	1.1	14
236	TiO2/HfO2 Bi-Layer Gate Stacks Grown by Atomic Layer Deposition for Germanium-Based Metal-Oxide-Semiconductor Devices Using GeOxNy Passivation Layer. Electrochemical and Solid-State Letters, 2011, 14, G27.	2.2	14
237	Solution derived ZnO:Al films with low resistivity. Thin Solid Films, 2012, 524, 81-85.	0.8	14
238	Synthesis of a 3D network of Pt nanowires by atomic layer deposition on a carbonaceous template. Nanoscale, 2014, 6, 6939.	2.8	14
239	Transparent conducting oxide films of group V doped titania prepared by aqueous chemical solution deposition. Thin Solid Films, 2014, 555, 33-38.	0.8	14
240	Amorphous and perovskite Li3xLa(2/3)â^'xTiO3 (thin) films via chemical solution deposition: solid electrolytes for all-solid-state Li-ion batteries. Journal of Sol-Gel Science and Technology, 2015, 73, 536-543.	1.1	14
241	Electrodeposition of Adherent Submicron to Micron Thick Manganese Dioxide Films with Optimized Current Collector Interface for 3D Li-Ion Electrodes. Journal of the Electrochemical Society, 2017, 164, D954-D963.	1.3	14
242	The influence of alloying on the phase formation sequence of ultra-thin nickel silicide films and on the inheritance of texture. Journal of Applied Physics, 2018, 123, 185302.	1.1	14
243	Micro-Transfer-Printing of Al₂O₃-Capped Short-Wave-Infrared PbS Quantum Dot Photoconductors. ACS Applied Nano Materials, 2019, 2, 299-306.	2.4	14
244	Thermal and Plasma-Enhanced Atomic Layer Deposition of Yttrium Oxide Films and the Properties of Water Wettability. ACS Applied Materials & Interfaces, 2020, 12, 3179-3187.	4.0	14
245	Atomic Layer Deposition of Nitrogen-Doped Al Phosphate Coatings for Li-Ion Battery Applications. ACS Applied Materials & Interfaces, 2020, 12, 25949-25960.	4.0	14
246	Nucleation and diffusion during growth of ternary Co1â^'xNixSi2 thin films studied by complementary techniques in real time. Journal of Applied Physics, 2008, 104, 093533.	1.1	13
247	Creation of gallium acid and platinum metal sites in bifunctional zeolite hydroisomerization and hydrocracking catalysts by atomic layer deposition. Catalysis Science and Technology, 2020, 10, 1778-1788.	2.1	13
248	A deep-level transient spectroscopy study of Co- and Ni-germanided n-type germanium. Materials Science in Semiconductor Processing, 2006, 9, 554-558.	1.9	12
249	Growth of pinhole-free ytterbium silicide film by solid-state reaction on Si(001) with a thin amorphous Si interlayer. Journal of Applied Physics, 2007, 102, 033508.	1.1	12
250	<i>In situ</i> study of the formation of silicide phases in amorphous Niâ€"Si mixed layers. Journal of Applied Physics, 2009, 106, .	1.1	12
251	Texture of CoSi2 films on Si(111), (110) and (001) substrates. Thin Solid Films, 2010, 519, 1277-1284.	0.8	12
252	Seed Layer and Multistack Approaches to Reduce Leakage in SrTiO3-Based Metalâ€"Insulatorâ€"Metal Capacitors Using TiN Bottom Electrode. Japanese Journal of Applied Physics, 2010, 49, 04DD01.	0.8	12

#	Article	IF	Citations
253	Structural and Kinetic Study of the Reduction of CuOâ€"CeO2/Al2O3 by Time-Resolved X-ray Diffraction. Catalysis Letters, 2012, 142, 959-968.	1.4	12
254	Size- and composition-controlled Ptâ€"Sn bimetallic nanoparticles prepared by atomic layer deposition. RSC Advances, 2017, 7, 20201-20205.	1.7	12
255	Plasma-enhanced atomic layer deposition of vanadium phosphate as a lithium-ion battery electrode material. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	12
256	Formation and stability of an active PdZn nanoparticle catalyst on a hydrotalcite-based support for ethanol dehydrogenation. Catalysis Science and Technology, 2017, 7, 3715-3727.	2.1	12
257	Oxidation barrier of Cu and Fe powder by Atomic Layer Deposition. Surface and Coatings Technology, 2018, 349, 1032-1041.	2.2	12
258	Plasma-Enhanced Atomic Layer Deposition of Nanostructured Gold Near Room Temperature. ACS Applied Materials & Interfaces, 2019, 11, 37229-37238.	4.0	12
259	Electrical characterization of Ar-ion-bombardment-induced damage in Au/Si and PtSi/Si Schottky barrier contacts. Semiconductor Science and Technology, 2001, 16, 83-90.	1.0	11
260	TaCN growth with PDMAT and H2/Ar plasma by plasma enhanced atomic layer deposition. Microelectronic Engineering, 2011, 88, 646-650.	1.1	11
261	Determination of activation energies of the U(Mo)/Si and U(Mo)/Al solid state reaction using in-situ X-ray diffraction and Kissinger analysis. Solid State Sciences, 2012, 14, 1133-1140.	1.5	11
262	AlSi matrices for U(Mo) dispersion fuel plates. Journal of Nuclear Materials, 2013, 439, 7-18.	1.3	11
263	Formation and texture of palladium germanides studied by in situ X-ray diffraction and pole figure measurements. Thin Solid Films, 2014, 551, 86-91.	0.8	11
264	Influence of carbon content on the copper-telluride phase formation and on the resistive switching behavior of carbon alloyed Cu-Te conductive bridge random access memory cells. Journal of Applied Physics, 2014, 115, 054501.	1.1	11
265	Phase formation in intermixed Niâ€"Ge thin films: Influence of Ge content and low-temperature nucleation of hexagonal nickel germanides. Microelectronic Engineering, 2014, 120, 168-173.	1.1	11
266	Atomic Layer Deposition of SnO2-Based Composite Anodes for Thin-Film Lithium-Ion Batteries. Frontiers in Energy Research, 2020, 8, .	1.2	11
267	Ballistic electron emission microscopy studies of the temperature dependence of Schottky barrier height distribution in CoSi2/n-Si(100) diodes formed by solid phase reaction. Solid-State Electronics, 2000, 44, 2217-2223.	0.8	10
268	Transient and end silicide phase formation in thin film Ni/polycrystalline-Si reactions for fully silicided gate applications. Applied Physics Letters, 2007, 91, 172108.	1.5	10
269	Point-Defect Generation in Ni-, Pd-, and Pt-Germanide Schottky Barriers on n-Type Germanium. Journal of the Electrochemical Society, 2007, 154, H857.	1.3	10
270	High-k Dielectrics and Metal Gates for Future Generation Memory Devices. ECS Transactions, 2009, 19, 29-40.	0.3	10

#	Article	IF	Citations
271	Fermi Level Depinning Failure for Al/GeO2/Ge Contacts. ECS Solid State Letters, 2012, 1, P79-P81.	1.4	10
272	Band alignment in Ge/GeOx/HfO2/TiO2 heterojunctions as measured by hard x-ray photoelectron spectroscopy. Applied Physics Letters, 2012, 101, .	1.5	10
273	3D porous nanostructured platinum prepared using atomic layer deposition. Journal of Materials Chemistry A, 2017, 5, 19007-19016.	5.2	10
274	Designing Nanoparticles and Nanoalloys for Gas-Phase Catalysis with Controlled Surface Reactivity Using Colloidal Synthesis and Atomic Layer Deposition. Molecules, 2020, 25, 3735.	1.7	10
275	Deep level transient spectroscopy study of Pd and Pt sputtering damage in n-type germanium. Applied Physics Letters, 2006, 89, 202114.	1.5	9
276	Oxidation suppression in ytterbium silicidation by Tiâˆ•TiN bicapping layer. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 285-289.	0.9	9
277	Kinetics of Ni3Si2 formation in the Ni2Siâ€"NiSi thin film reaction from in situ measurements. Applied Physics Letters, 2007, 91, 232102.	1.5	9
278	Yttrium silicide formation and its contact properties on Si(100). Microelectronic Engineering, 2008, 85, 131-135.	1.1	9
279	Simultaneous real-time x-ray diffraction spectroscopy, Rutherford backscattering spectrometry, and sheet resistance measurements to study thin film growth kinetics by Kissinger plots. Journal of Applied Physics, 2008, 104, 103538.	1.1	9
280	Crystallization resistance of barium titanate zirconate ultrathin films from aqueous CSD: a study of cause and effect. Journal of Materials Chemistry, 2009, 19, 1115.	6.7	9
281	In situ and ex situ investigation on the annealing performance of the ZnO film grown by ion beam deposition. Journal of Materials Science: Materials in Electronics, 2010, 21, 88-95.	1.1	9
282	Effective Schottky Barrier Height Modulation by an Ultrathin Passivation Layer of GeOxNy for Alâˆ•n-Ge(100) Contact. Electrochemical and Solid-State Letters, 2011, 14, H487.	2.2	9
283	Electron barrier height at CuxTe1âˆ'x/Al2O3 interfaces of conducting bridge memory stacks. Thin Solid Films, 2013, 533, 34-37.	0.8	9
284	Annealing of sulfide stabilized colloidal semiconductor nanocrystals. Journal of Materials Chemistry C, 2014, 2, 178-183.	2.7	9
285	Visualization and classification of epitaxial alignment at hetero-phase boundaries. Thin Solid Films, 2016, 599, 104-112.	0.8	9
286	Se-containing inks for the formation of CuInSe2 films without gas-phase selenization. Solar Energy Materials and Solar Cells, 2016, 145, 126-133.	3.0	9
287	Ternary silicide formation from Ni-Pt, Ni-Pd and Pt-Pd alloys on Si(100): Nucleation and solid solubility of the monosilicides. Acta Materialia, 2017, 130, 19-27.	3.8	9
288	Effect of thermal annealing and chemical treatments on secondary electron emission properties of atomic layer deposited MgO. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, 06A102.	0.9	9

#	Article	IF	Citations
289	In Situ Photoluminescence of Colloidal Quantum Dots During Gas Exposureâ€"The Role of Water and Reactive Atomic Layer Deposition Precursors. ACS Applied Materials & Interfaces, 2019, 11, 26277-26287.	4.0	9
290	The effect of sputtered W-based carbide diffusion barriers on the thermal stability and void formation in copper thin films. Microelectronic Engineering, 2010, 87, 2535-2539.	1.1	8
291	Annealing induced hysteresis suppression for TiN/HfO₂/GeON/p-Ge capacitor. Semiconductor Science and Technology, 2011, 26, 125003.	1.0	8
292	Sealed ultra low-k organosilica films with improved electrical, mechanical and chemical properties. Journal of Materials Chemistry C, 2013, 1, 3961.	2.7	8
293	Synthesis and Characterization of Photoreactive TiO₂â€"Carbon Nanosheet Composites. Journal of Physical Chemistry C, 2014, 118, 21031-21037.	1.5	8
294	Conductive filaments multiplicity as a variability factor in CBRAM. , 2015, , .		8
295	Kinetics of Multiâ€Step Redox Processes by Timeâ€Resolved In Situ Xâ€ray Diffraction. Chemie-Ingenieur-Technik, 2016, 88, 1684-1692.	0.4	8
296	Tuning the switching behavior of conductive-bridge resistive memory by the modulation of the cation-supplier alloys. Microelectronic Engineering, 2017, 167, 47-51.	1.1	8
297	Perpendicular magnetic anisotropy of CoFeBTa bilayers on ALD HfO2. AIP Advances, 2017, 7, 055933.	0.6	8
298	Aluminum tri-isopropoxide as an alternative precursor for atomic layer deposition of aluminum oxide thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	8
299	Switchable Piezoresistive SmS Thin Films on Large Area. Sensors, 2019, 19, 4390.	2.1	8
300	Impurity-enhanced solid-state amorphization: the Niâ€"Si thin film reaction altered by nitrogen. Journal Physics D: Applied Physics, 2019, 52, 145301.	1.3	8
301	Chemical and Structural Configuration of Pt-Doped Metal Oxide Thin Films Prepared by Atomic Layer Deposition. Chemistry of Materials, 2019, 31, 9673-9683.	3.2	8
302	Assessing stability of metal tellurides as alternative photomask materials for extreme ultraviolet lithography. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2019, 37, 061607.	0.6	8
303	A Secondary Reaction Pathway for the Alumina Atomic Layer Deposition Process with Trimethylaluminum and Water, Revealed by Full-Range, Time-Resolved In Situ Mass Spectrometry. Journal of Physical Chemistry C, 2020, 124, 26443-26454.	1.5	8
304	<i>In situ</i> study of the thermal stability of supported Pt nanoparticles and their stabilization <i>via</i> atomic layer deposition overcoating. Nanoscale, 2020, 12, 11684-11693.	2.8	8
305	Plasma enhanced atomic layer deposition of a (nitrogen doped) Ti phosphate coating for improved energy storage in Li-ion batteries. Journal of Power Sources, 2021, 497, 229866.	4.0	8
306	Mitigation of photon background in nanoplasmonic all-on-chip Raman sensors. Optics Express, 2020, 28, 33564.	1.7	8

#	Article	IF	Citations
307	Tuning of the thermal stability and ovonic threshold switching properties of GeSe with metallic and non-metallic alloying elements. Journal of Applied Physics, 2021, 130, .	1.1	8
308	Nondestructive characterization of thin silicides using x-ray reflectivity. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 470-476.	0.9	7
309	In situ X-ray diffraction study of thin film Ir/Si solid state reactions. Microelectronic Engineering, 2010, 87, 258-262.	1.1	7
310	The Inhibition of Enhanced Cu Oxidation on Rutheniumâˆ•Diffusion Barrier Layers for Cu Interconnects by Carbon Alloying into Ru. Journal of the Electrochemical Society, 2011, 158, H1228.	1.3	7
311	VO₂, a Metal-Insulator Transition Material for Nanoelectronic Applications. ECS Transactions, 2012, 45, 151-158.	0.3	7
312	Wetting transitions of polymers via thermal and plasma enhanced atomic layer depositions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, .	0.9	7
313	On the formation and structural properties of hexagonal rare earth (Y, Gd, Dy, Er and Yb) disilicide thin films. Journal of Alloys and Compounds, 2014, 611, 149-156.	2.8	7
314	Stuffing-enabled surface confinement of silanes used as sealing agents on CF4 plasma-exposed 2.0 p-OSG films. Microelectronic Engineering, 2015, 137, 70-74.	1.1	7
315	Effectiveness of Ligand Denticity-Dependent Oxidation Protection in Copper MOD Inks. Langmuir, 2019, 35, 16101-16110.	1.6	7
316	Corrosion protection of Cu by atomic layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, 060902.	0.9	7
317	Photocatalytic Lithography with Atomic Layerâ€“Deposited TiO₂ Films to Tailor Biointerface Properties. Advanced Materials Interfaces, 2019, 6, 1900035.	1.9	7
318	Controlled synthesis of Feâ€“Pt nanoalloys using atomic layer deposition. Nanotechnology, 2021, 32, 095602.	1.3	7
319	Atomic layer deposition of metal phosphates. Applied Physics Reviews, 2022, 9, .	5.5	7
320	Electrical characterization of NiSi/Si interfaces formed by a single and a two-step rapid thermal silicidation. Semiconductor Science and Technology, 2005, 20, 716-719.	1.0	6
321	0.5 nm EOT low leakage ALD SrTiO<inf>3</inf> on TiN MIM capacitors for DRAM applications. , 2008, , .		6
322	(Invited) Introducing Lanthanide Aluminates as Dielectrics for Nonvolatile Memory Applications: A Material Scientist's View. ECS Transactions, 2010, 33, 31-42.	0.3	6
323	In situ study of the growth properties of Ni-rare earth silicides for interlayer and alloy systems on Si(100). Journal of Applied Physics, 2012, 111, 043511.	1.1	6
324	In Situ Study of ALD Processes Using Synchrotron-based X-ray Fluorescence and Scattering Techniques. ECS Transactions, 2013, 50, 35-42.	0.3	6

#	Article	IF	Citations
325	Formation of ultrathin Ni germanides: solid-phase reaction, morphology and texture. Journal Physics D: Applied Physics, 2017, 50, 455301.	1.3	6
326	Formation and Functioning of Bimetallic Nanocatalysts: The Power of Xâ€ray Probes. Angewandte Chemie, 2019, 131, 13354-13364.	1.6	6
327	The co-reactant role during plasma enhanced atomic layer deposition of palladium. Physical Chemistry Chemical Physics, 2020, 22, 9124-9136.	1.3	6
328	Converting molecular layer deposited alucone films into Al₂O₃/alucone hybrid multilayers by plasma densification. Dalton Transactions, 2021, 50, 1224-1232.	1.6	6
329	Impact of changes in bond structure on ovonic threshold switching behaviour in GeSe₂. Journal of Materials Chemistry C, 2021, 9, 117-126.	2.7	6
330	Ion beam modification of the Ni-Si solid-phase reaction: The influence of substrate damage and nitrogen impurities introduced by ion implantation. Journal Physics D: Applied Physics, 2021, 54, 015307.	1.3	6
331	Kinetics of agglomeration of NiSi and NiSi2 phase formation.. Materials Research Society Symposia Proceedings, 2002, 745, 4121.	0.1	5
332	Metal In-Diffusion during Fe and Co-Germanidation of Germanium. Solid State Phenomena, 2008, 131-133, 47-52.	0.3	5
333	In situ study of the formation of silicide phases in amorphous Coâ€“Si mixed layers. Microelectronic Engineering, 2010, 87, 282-285.	1.1	5
334	Non-linear dielectric constant increase with Ti composition in high-k ALD-HfTiOxfilms after O2crystallization annealing. IOP Conference Series: Materials Science and Engineering, 2010, 8, 012023.	0.3	5
335	Interfacial reactions of Gd- and Nb-oxide based high-k layers deposited by aqueous chemical solution deposition. Microelectronic Engineering, 2011, 88, 1338-1341.	1.1	5
336	Study of Schottky barrier height modulation for NiSi/Si contact with an antimony interlayer. Microelectronic Engineering, 2013, 106, 121-124.	1.1	5
337	On the nucleation of PdSi and NiSi2 during the ternary Ni(Pd)/Si(100) reaction. Journal of Applied Physics, 2013, 114, .	1.1	5
338	Plasma Enhanced Atomic Layer Deposition on Powders. ECS Transactions, 2014, 64, 51-62.	0.3	5
339	Modification of Ultra Low-k Dielectric Films by O₂and CO₂Plasmas. ECS Journal of Solid State Science and Technology, 2015, 4, N3048-N3057.	0.9	5
340	Axiotaxy and epitaxial textures in C54-TiSi₂ films on Si(0â€‰0â€‰1) and Si(1â€‰1â€‰1) substrates. Journal Physics D: Applied Physics, 2018, 51, 445302.	1.3	5
341	Atomic layer deposition of thin films as model electrodes: A case study of the synergistic effect in Fe2O3-SnO2. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, 050904.	0.9	5
342	Reaction Pathways for Atomic Layer Deposition with Lithium Hexamethyl Disilazide, Trimethyl Phosphate, and Oxygen Plasma. Journal of Physical Chemistry C, 2020, 124, 27829-27839.	1.5	5

#	Article	IF	Citations
343	Emergence of Metallic Conductivity in Ordered One-Dimensional Coordination Polymer Thin Films upon Reductive Doping. ACS Applied Materials & Interfaces, 2021, 13, 10249-10256.	4.0	5
344	The Texture of Thin NiSi Films and Its Effect on Agglomeration. Ceramic Transactions, 0, , 1-9.	0.1	5
345	A limitation map of performance for porous electrodes in lithium-ion batteries. IScience, 2021, 24, 103496.	1.9	5
346	Influence of alloying the copper supply layer on the retention of CBRAM. , 2015, , .		4
347	Anisotropic thermal expansion of Ni, Pd and Pt germanides and silicides. Journal Physics D: Applied Physics, 2016, 49, 275307.	1.3	4
348	Influence of the Chalcogen Element on the Filament Stability in CuIn(Te,Se,S)₂/Al₂O₃ Filamentary Switching Devices. ACS Applied Materials & Interfaces, 2018, 10, 14835-14842.	4.0	4
349	Formation and preferential orientation of Au-free Al/Ti-based ohmic contacts on different hexagonal nitride-based heterostructures. Journal of Applied Physics, 2020, 127, 215701.	1.1	4
350	Tuning size and coverage of Pd nanoparticles using atomic layer deposition. Applied Surface Science, 2021, 539, 148238.	3.1	4
351	U(Mo) grain refinement induced by irradiation with high energy iodine. Journal of Nuclear Materials, 2021, 548, 152850.	1.3	4
352	Plasma-enhanced atomic layer deposition: Correlating O2 plasma parameters and species to blister formation and conformal film growth. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	0.9	4
353	Selective Vapor-Phase Doping of Pt Nanoparticles into Phase-Controlled Nanoalloys. Journal of Physical Chemistry C, 2022, 126, 1426-1438.	1.5	4
354	Titanium Carboxylate Molecular Layer Deposited Hybrid Films as Protective Coatings for Lithium-Ion Batteries. ACS Applied Materials & Interfaces, 2022, 14, 24908-24918.	4.0	4
355	Growth of patterned thin epitaxial CoSi2-films by a titanium oxide mediated epitaxy process. Thin Solid Films, 2000, 380, 201-203.	0.8	3
356	Does line-edge roughness matter?: FEOL and BEOL perspectives. , 2003, , .		3
357	Applications of synchrotron X-rays in microelectronics industry research. Nuclear Instruments & Methods in Physics Research B, 2005, 241, 247-252.	0.6	3
358	Texture in Thin Films. Materials Science Forum, 2005, 495-497, 1333-1342.	0.3	3
359	Point-Defect Generation in Ni-, Pd-, and Pt-Germanided Schottky Barriers on N-Type Germanium Substrates. ECS Transactions, 2006, 3, 391-400.	0.3	3
360	Stress evolution during Niâ€œSi compound formation for fully silicided (FUSI) gates. Microelectronic Engineering, 2007, 84, 2533-2536.	1.1	3

#	Article	IF	Citations
361	Formation and stability of NiSi in the presence of Co and Fe alloying elements. Journal of Vacuum Science & Technology B, 2008, 26, 1971-1977.	1.3	3
362	Improved Diffusion Barrier Properties and NiSi Thermal Stability for the Cu Contact with the Ru/TaSiN Stack on NiSi/Si. ECS Solid State Letters, 2012, 2, P1-P3.	1.4	3
363	Improved Thermal Stability and Electrical Performance by Using PEALD Ultrathin Al2O3 Film with Ta as Cu Diffusion Barrier on Low k Dielectrics. ECS Solid State Letters, 2012, 1, P54-P56.	1.4	3
364	Pore Narrowing of Mesoporous Silica Materials. Materials, 2013, 6, 570-579.	1.3	3
365	Effect of high temperature deposition on CoSi2 phase formation. Journal of Applied Physics, 2013, 113, 234902.	1.1	3
366	Study of amorphous Cuâ€“Teâ€“Si thin films showing high thermal stability for application as a cation supply layer in conductive bridge random access memory devices. RSC Advances, 2016, 6, 32106-32114.	1.7	3
367	The role of composition and microstructure in Niâ€“W silicide formation and low temperature epitaxial NiSi2 growth by premixing Si. Journal Physics D: Applied Physics, 2017, 50, 065303.	1.3	3
368	Axiotaxy in oxide heterostructures: Preferential orientation of BaCeO3 nanoparticles embedded in superconducting YBa2Cu3O7â˜’ thin films. Thin Solid Films, 2017, 638, 105-113.	0.8	3
369	A liquid alkoxide precursor for the atomic layer deposition of aluminum oxide films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	0.9	3
370	Plasma-enhanced atomic layer deposition of nickel and cobalt phosphate for lithium ion batteries. Dalton Transactions, 2022, 51, 2059-2067.	1.6	3
371	Atomic layer deposition of ternary ruthenates by combining metalorganic precursors with RuO₄ as the co-reactant. Dalton Transactions, 2022, 51, 10721-10727.	1.6	3
372	Shuffling Atomic Layer Deposition Gas Sequences to Modulate Bimetallic Thin Films and Nanoparticle Properties. Chemistry of Materials, 2022, 34, 6142-6154.	3.2	3
373	Silicide Formation for Ni and Pd Bilayers on Si(100) Substrates. Materials Research Society Symposia Proceedings, 2001, 670, 1.	0.1	2
374	Nanometer patterning of thin CoSi2-films by application of local stress. Microelectronic Engineering, 2001, 55, 177-182.	1.1	2
375	Defect Characterization of the Structure-Growth Zone-Model for Sputter Deposited Cu Films. Materials Science Forum, 2004, 445-446, 69-71.	0.3	2
376	Alternative Catalysts For Si-Technology Compatible Growth Of Si Nanowires. Materials Research Society Symposia Proceedings, 2007, 1017, 14.	0.1	2
377	Oxygen sensing with ZnO thin films. , 2011, , .		2
378	TaNâˆ•Ta as an Effective Diffusion Barrier for Direct Contact of Copper and NiSi. Electrochemical and Solid-State Letters, 2012, 15, H9.	2.2	2

#	Article	IF	Citations
379	Sealing of low-k dielectric (k=2.0) with self-assembled monolayers (SAMs) for the atomic layer deposition (ALD) of TiN. Materials Research Society Symposia Proceedings, 2013, 1559, 1.	0.1	2
380	Electro-precipitation via oxygen reduction: a new technique for thin film manganese oxide deposition. Journal of Materials Chemistry A, 2016, 4, 13555-13562.	5.2	2
381	Kinetics of Lifetime Changes in Bimetallic Nanocatalysts Revealed by Quick Xâ€ray Absorption Spectroscopy. Angewandte Chemie, 2018, 130, 12610-12614.	1.6	2
382	Reaction mechanism of the Me₃AuPMe₃â€“H₂ plasma-enhanced ALD process. Physical Chemistry Chemical Physics, 2020, 22, 11903-11914.	1.3	2
383	Atomic Layer Deposition of Localized Boron- and Hydrogen-Doped Aluminum Oxide Using Trimethyl Borate as a Dopant Precursor. Chemistry of Materials, 2020, 32, 4152-4165.	3.2	2
384	ALD Pt nanoparticles and thin-film coatings enhancing the stability and performance of silicon photocathodes for solar water splitting. Sustainable Energy and Fuels, 2021, 5, 3115-3123.	2.5	2
385	An IR Spectroscopy Study of the Degradation of Surface Bound Azido-Groups in High Vacuum. Langmuir, 2021, 37, 12608-12615.	1.6	2
386	An atomic force microscopy study of thin CoSi/sub 2/ films formed by solid state reaction. , 0, , .		1
387	The Influence of Ti Capping Layers on CoSi₂ Formation in the Presence of Interfacial Oxide. Materials Research Society Symposia Proceedings, 1999, 564, 139.	0.1	1
388	Formation and Characterization of Spe Grown Ultra-Thin Cobalt Disilicide Film. Materials Research Society Symposia Proceedings, 1999, 564, 157.	0.1	1
389	A Beem Study of PtSi Schottky Contacts on Ion-Milled Si. Materials Research Society Symposia Proceedings, 1999, 564, 201.	0.1	1
390	CoSi2 formation using a Ti capping layer - The influence of processing conditions on CoSi2 nucleation.. Materials Research Society Symposia Proceedings, 2001, 670, 1.	0.1	1
391	The dependence of the etching property of CoSi2 films in diluted HF solutions on the formation conditions. Applied Surface Science, 2001, 178, 44-49.	3.1	1
392	Orientation-dependent stress build-up during the formation of epitaxial CoSi2. Microelectronic Engineering, 2001, 55, 145-150.	1.1	1
393	Linear growth of Ni2Si thin film on n+/p junction at low temperature. Journal of Materials Research, 2006, 21, 3017-3021.	1.2	1
394	Edge-to-edge matching in thin films. Metallurgical and Materials Transactions A: Physical Metallurgy and Materials Science, 2006, 37, 851-855.	1.1	1
395	Fundamentals of Intrinsic Stress during Silicide Formation. AIP Conference Proceedings, 2007, , .	0.3	1
396	In situ x-ray diffraction study of Niâ€“Yb interlayer and alloy systems on Si(100). Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2010, 28, 20-26.	0.9	1

#	Article	IF	Citations
397	Texture Effects in Solid-State Reactions of Thin Films. Materials Science Forum, 0, 706-709, 2857-2862.	0.3	1
398	(Invited) Optimization of WAl2O3Cu(-Te) Material Stack for High-Performance Conductive-Bridging Memory Cells. ECS Transactions, 2013, 58, 175-180.	0.3	1
399	(Invited) Atomic Layer Deposition of Nanoalloys of Noble and Non-Noble Metals. ECS Transactions, 2017, 80, 97-106.	0.3	1
400	Covalent graphite modification by low-temperature photocatalytic oxidation using a titanium dioxide thin film prepared by atomic layer deposition. Catalysis Science and Technology, 2021, 11, 6724-6731.	2.1	1
401	Edge-to-edge matching in thin films. Metallurgical and Materials Transactions A: Physical Metallurgy and Materials Science, 2006, 37, 851-855.	1.1	1
402	Inherent Area-Selective Growth and Nucleation Enhancement during Ru ALD Using the RuO₄-Precursor and H₂-Gas. ECS Meeting Abstracts, 2018, MA2018-02, 984-984.	0.0	1
403	Non-destructive characterization of thin silicides using X-ray reflectivity. , 0, , .		0
404	Ion-bombardment effects on PtSi/n-Si Schottky contacts studied by ballistic electron emission microscopy. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2000, 18, 1942.	1.6	0
405	The effect of Pd addition on silicide formation for Ni/Pd bilayers on silicon. , 0, , .		0
406	Room temperature grain growth in sputtered Cu films. Materials Research Society Symposia Proceedings, 2002, 749, 1.	0.1	0
407	Texture of silicide films on Si[001] : the occurrence of axiotaxy in cubic CoSi/sub 2/, tetragonal Î±-FeSi/sub 2/ and orthorhombic NiSi. , 0, , .		0
408	Reactive Diffusion in the Ni-Si System: Influence of Ni Thickness on the Phase Formation Sequence. ECS Meeting Abstracts, 2005, , .	0.0	0
409	Edge-to-edge matching in thin films. Metallurgical and Materials Transactions A: Physical Metallurgy and Materials Science, 2006, 37, 851-855.	1.1	0
410	Phase formation and stability of Ni silicide contacts - scaling to ultra-thin films. , 2010, , .		0
411	Wet-Chemical Synthesis of 3D Stacked Thin Film Metal-Oxides for All-Solid-State Li-Ion Batteries. Materials, 2017, 10, 1072.	1.3	0
412	Use of Neutron Absorbers to Influence the Neutron Transmutation Doping Process in Silicon. Nuclear Technology, 2020, 206, 758-765.	0.7	0
413	Texture analysis of silicide thin films: combining statistical and microscopical information. , 2008, , 365-366.		0
414	(Invited) Ultrathin Epitaxial Silicides for Semiconductor Contacts. ECS Meeting Abstracts, 2017, , .	0.0	0

#	Article	IF	Citations
415	Molecular Layer Deposition for Applications in Lithium-Ion Batteries. ECS Meeting Abstracts, 2017, , .	0.0	0
416	(Invited) Atomic Layer Deposition of Nanoalloys of Noble and Non-Noble Metals. ECS Meeting Abstracts, 2017, , .	0.0	0
417	Conformal Vanadium Oxides Beyond Crystalline V2O5 As High Energy Density 3D Thin-Film Electrodes for Lithium-Ion Batteries. ECS Meeting Abstracts, 2017, , .	0.0	0
418	(Invited) Atomic Layer Deposition for Interface Engineering of (Thin-Film) Lithium-Ion Battery. ECS Meeting Abstracts, 2018, , .	0.0	0
419	Synthesis of 3D Porous Nanostructured Platinum Using Atomic Layer Deposition. ECS Meeting Abstracts, 2018, , .	0.0	0
420	(Invited) Red Fluoride Phosphors: A Story of Reliability. ECS Meeting Abstracts, 2018, , .	0.0	0
421	Electrodeposition of Adherent MnO2 Films with Optimized Current Collector Interface for 3D Li-Ion Electrodes. ECS Meeting Abstracts, 2018, , .	0.0	0
422	Near Room Temperature PE-ALD of Nanostructured Gold for Enhanced Raman Scattering. ECS Meeting Abstracts, 2019, , .	0.0	0
423	Impact of Atomic Layer Deposition on the Photoluminescence of Colloidal Quantum Dots. ECS Meeting Abstracts, 2019, , .	0.0	0
424	(Invited) A Tutorial on Atomic Layer Deposition and Its Application in Lithium-Ion Batteries. ECS Meeting Abstracts, 2019, , .	0.0	0
425	(Invited) ALD and MLD of Functional Thin-Film Coatings for Enhanced Performance in Li-Ion and Li-Metal Solid-State Batteries. ECS Meeting Abstracts, 2019, , .	0.0	0
426	Surface reactions between LiHMDS, TMA and TMP leading to deposition of amorphous lithium phosphate. Journal of Materials Chemistry A, 2022, 10, 3543-3551.	5.2	0
427	Aligning time-resolved kinetics (TAP) and surface spectroscopy (AP-XPS) for a more comprehensive understanding of ALD-derived 2D and 3D model catalysts.. Faraday Discussions, 2022, , .	1.6	0
428	(Invited) MLD of Metal-Organic Thin Films with Tunable Conductance for Neuromorphic Computing Applications. ECS Meeting Abstracts, 2020, MA2020-02, 1683-1683.	0.0	0